High-quality planar high- T_c Josephson junctions

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(Received 25 April 2005; accepted 25 July 2005; published online 29 August 2005)

Reproducible high- T_c Josephson junctions have been made in a rather simple two-step process using ion irradiation. A microbridge (1 to 5 μ m wide) is firstly designed by ion irradiating a *c*-axis-oriented YBa₂Cu₃O_{7- δ} film through a gold mask such as the nonprotected part becomes insulating. A lower T_c part is then defined within the bridge by irradiating with a much lower fluence through a narrow slit (20 nm) opened in a standard electronic photoresist. These planar junctions, whose settings can be finely tuned, exhibit reproducible and nearly ideal Josephson characteristics. This process can be used to produce complex Josephson circuits. © 2005 American Institute of *Physics*. [DOI: 10.1063/1.2037206]

For the last fifteen years or so, a great deal of research have been devoted to high- T_c superconducting (HTSc) Josephson junctions (JJ) for electronic applications.¹ Two main techniques have been used: The so-called grain-boundary junctions and the edge junctions. Both of them require special substrates, which strongly limit the design of complex circuits, and delicate processing, which impairs their reproducibility, and therefore their applications. An alternative process has been proposed to create weak links on purpose. The atomic disorder induced by ion irradiation drives HTSc cuprates toward an insulating state; for intermediate disorder, the T_c is lowered and the resistivity is increased.^{2,3} Authors already succeeded in making superconductor-normalsuperconductor junctions by lowering locally the T_c of a HTSc film.⁴ They obtained rather good Josephson characteristics, but the overall process was rather complex still.

Here, we present an original method to make HTSc JJ. A t=150 nm thick *c*-axis-oriented YBa₂Cu₃O_{7- δ} (YBCO) film is pulsed laser deposited and *in situ* covered by a 40 nm thick gold layer to insure both low contact resistances to the junction and reproducible characteristics. Poly(methylmethacrylate) (PMMA) photoresist is then deposited and patterned to design microbridges, (1 to 5 μ m wide, 8 to 40 μ m long). A 250 nm thick gold layer is deposited and lifted-off, such as the microbridges and the contacts remain covered. The in situ gold layer is removed by Ar-ion beam etching (IBE). The sample is then ion irradiated with 110 keV oxygen; the 5×10^{15} atoms/cm² fluence makes the unprotected parts insulating, therefore designing a current path underneath the gold layer including the bridges and the contact pads. No HTSc material is removed during this process. In a second step, gold above the microbridge is removed by Ar IBE through a suitable PMMA mask. Finally, photoresist is deposited all over the sample, and a narrow slit (20 nm width)

is opened across the microbridge which will defined the junction area. 100 keV oxygen ions are used to lower the T_c in this region, with typical fluences of a few 10^{13} atoms/cm². We therefore end with a junction completely embedded in a cuprate layer, contacted with *in situ* low resistance gold pads. No further annealing or heat treatment is needed to obtain the characteristics described below, as opposed to previous studies.⁵

In the inset (a) of Fig. 3 is displayed the resistance as a function of temperature for two 1 μ m width bridges irradiated with 3 and 6×10^{13} atoms/cm², and measured with a tiny current: The highest transition refers to that of the electrodes (the same as the unprocessed film), and the lowest, which can be tuned by the fluence, to the junctions themselves. The resistances of the bridges are the same within 10%, which gives an order of magnitude of their geometrical dispersion. The transitions being sharp ($\Delta T = 1-2$ K), one can precisely adjust the operation temperature of the device. Let us emphasize that the observed transition corresponds to the Josephson coupling T_J of the two electrodes and *not* the transition of the irradiated part itself. As a matter of fact, the inset Fig. 1 shows the current-voltage (I-V) characteristics of a junction at different temperatures. At high temperature, just below the observed zero resistance state in the inset (a) of Fig. 3, a typical resistively shunted junction (RSJ)-like behavior is observed⁶ with an upward curvature of the dissipative branch, indicating a Josephson coupling of the two electrodes through a normal layer. When lowering the temperature, the I-V characteristics display a downward curvature as expected for a flux flow regime. The temperature which separates the two regimes is T'_{c} , the critical temperature of the irradiated part $[32(\pm 1)K$ in this case].

The critical current of the junctions $I_c(T)$ shows a quadratic dependence as a function of temperature (solid lines in Fig. 1). This is consistent with previous studies,^{5,7} and follows the deGennes–Wertammer model of proximity effect.⁸ The coupling of the two pristine superconducting regions

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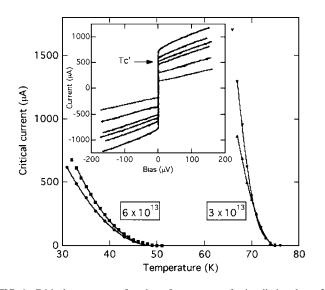


FIG. 1. Critical current as a function of temperature for irradiation doses 3 and 6×10^{13} ions/cm²: Two 5 μ m wide samples are displayed for each, and the solid lines are quadratic fits. Inset: current vs bias curves of a 5 μ m wide bridge irradiated with 6×10^{13} ions/cm² at different temperatures (*T*=29, 31, 32, 33, 36, and 40 K from top to bottom). At a high temperature, the upward curvature refers to RSJ-like behavior of a JJ. At a low temperature, the downward curvature is characteristic of a flux-flow regime. The arrow indicates T'_c estimated from this diagram.

occurs through the damaged one above its own T'_c ; Cooper pairs diffuse within a so-called "normal coherence length" $\xi_N(T)$, corresponding to the loss of phase coherence due to thermal excitations:

$$\xi_N(T) = \left(\frac{\hbar D}{2\pi k_B T}\right)^{1/2} \left(1 + \frac{2}{\ln(T/T_c')}\right)^{1/2},\tag{1}$$

where D is the diffusion constant. The critical current is therefore given by

$$I_c(T) = I_0 \left(1 - \frac{T}{T_J}\right)^2 \frac{\ell/\xi_N}{\sinh(\ell/\xi_N)},\tag{2}$$

where I_0 is a typical critical current, and ℓ the length of the normal part assuming a rectangular shape in first approximation. This behavior is valid (and observed) for temperatures above T'_c , of course. Since the temperature dependence of $\xi_N(T)$ itself is weak [sqrt(T) and log(T)], the main contribution to $I_c(T)$ comes from the divergence at T_J , and therefore follows a T^2 law. From the fitting procedure, one gets precisely T_J whose dispersion is low (less than 0.5 K for the 3 $\times 10^{13}$ atoms/cm², and 3 K for the 6×10^{13} atoms/cm² junctions). The typical parameters just below T_J , where the device will be operated [I_c , J_c (the critical current density) and the $I_c R_n$ product] are given in Table I. These numbers compare nicely to the actual performances of low- T_c junctions used for the rapid single flux quantum (RSFQ) logic, for

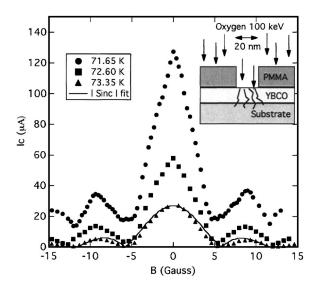


FIG. 2. Critical current as a function of the applied magnetic field on a 5 μ m wide junction irradiated at 3×10¹³ ions/cm², for different temperatures. Taking the zero-temperature London penetration depth as 140 nm, λ_J is calculated to be 1.9 μ m, 2.9 μ m, and 4.2 μ m for *T*=71.5 K, 72.5 K, and 73.5 K, respectively. Self-field effects show up when λ_J becomes of the order of the junction width. The solid line is a fit to a perfect Fraunhofer pattern for a rectangular junction in the small junction limit. The insert is a schematic side view of the irradiation process.

example.⁹ The high J_c values combined with a low R_n (insuring nonhysteretic behavior) look promising. Lastly, one can get from the fit the ratio $\ell/\xi_N(T_J)$, but the accuracy is poor since it enters in a slowly variating function [x/sh(x) at small x]. These two lengths are important: $\xi_N(T_J)$ is governed by the physics of the junction, and ℓ defines its geometrical properties. We will return to their determination later on.

The most stringent quality test for a JJ is the Fraunhofer pattern. In Fig. 2, is shown the modulation of the critical current of a junction as a function of the applied magnetic field for different temperatures. The curve at T=73.4 K is very close to |sinc(B)| as expected for a rectangular junction when its width W is smaller than the Josephson penetration length $\lambda_J = (\hbar/2\mu_0 e)^{1/2} (tW/I_c(2\lambda_L + \ell))^{1/2}$, where λ_L is the London penetration depth. Lowering the temperature makes the critical current increase and λ_J becoming smaller than *W*: The Owen and Scalapino model¹⁰ taking into account selffield effects in the junction gives rise to typical patterns as observed here (no cancellation of I_c and a less rounded pattern). Numerical comparisons of λ_I and W in these experiments nicely confirm this cross over (see caption legend of Fig. 2). Such an ideal behavior has not been reported in previous studies.^{4,5} The period of the modulation corresponds to one flux quantum in the junction provided λ_L is taken to be typical of thin films¹¹ (400 nm at 72 K).

TABLE I. Typical parameters for 5 μ m wide junctions.

| Sample | Fluence (atoms/cm ²) | T_j (K) | T_c' (K) | $\begin{array}{c} R_n(0.9T_j) \\ \times(\Omega) \end{array}$ | $I_c(0.9T_j) \times (\mu A)$ | $I_c R_n(0.9T_j) \times (\mu \mathrm{V})$ | $J_c(0.9T_j) \times (\mathrm{kA/cm}^2)$ |
|--------|-------------------------------------|-----------|------------|--|------------------------------|---|---|
| M11 | 6×10^{13} | 49 | 32 | 1.2 | 72 | 90 | 10 |
| M13 | 6×10^{13} | 48 | 31 | 1.2 | 90 | 72 | 12 |
| M21 | 3×10^{13} | 75 | 57 | 0.35 | 772 | 270 | 100 |
| M25 | 3×10^{13} | 75 | 61 | 0.25 | 1100 | 272 | 140 |

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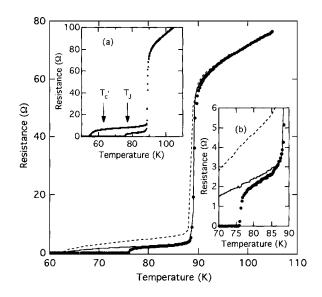


FIG. 3. Resistance as a function of temperature for a 1 μ m wide microbridge irradiated at 3×10¹³ ions/cm², computed with a 80 nm long junction (dotted line) or a 40 nm long one (solid line). The absolute value of R(100 K) has been adjusted within 5%. Inset (b): Blow-up of the main figure. Inset (a): R(T) for two 1 μ m wide bridges irradiated with 3 and 6 ×10¹³ ions/cm², respectively. The Josephson behavior is observed between T'_c and T_J , shown here for the lower fluence.

Besides the fact that we are able to make nice HTSc JJs in a rather simple process starting from blank *c*-axis-oriented YBCO films, let us emphasize that we can tailor their characteristics rather precisely. Choosing the operating temperature is quite easy by choosing the fluence, but what about the exact geometry of the device? It will control its electrical parameters as the normal state resistance and the critical current density. The geometry will be controlled first by the actual ion random walk within the sample, second by the modification of T_c and the resistivity ρ of the material by defects, and third by the proximity effect between the pristine region and the irradiated one. Using the TRIM code¹² and suitable assumptions, we have computed a Gaussian-type distribution of defects centered on the 20 nm wide slit whose standard deviation is roughly 80 nm,¹³ much smaller than a crude estimate of 150 nm or so,⁴ and in good agreement with experimental observations: The normal state resistance measured corresponds to the expected width of the channel within a few percents, even for the 1 μ m wide ones, confirming that the straggling is much smaller than this value. Based on the actual R(T) curve of a pristine channel, we have been able to compute the one of irradiated samples with a very good accuracy (Fig. 3). The increase in resistivity and the decrease in T_c as a function of the created defects have been taken from the literature.^{3,14–16} The resistance of the whole irradiated channel has been then calculated by integrating the resistivity over the defects distribution. As one can see in Fig. 3, the overall shape is good but the lowtemperature part deviates from the experimental data: The estimated resistance is higher, and T'_c is lower. This is due to the proximity effect and the Josephson coupling. A better result for the resistance is obtained if one uses a 40 nm standard deviation defects distribution, i.e., a full width at half maximum of 80 nm: This is the actual length of Junction ℓ . The superconducting state from the reservoirs tends to propagate beyond the actual defects profile, and makes ℓ shorter than crudely estimated. T_J is much higher than T'_c due to Josephson coupling. The difference between computed and experimental data is controlled by the proximity effect, and the temperature dependence of the coherence length $\xi_N(T)$ within the irradiated region. A self-consistent calculation is being made¹³ to get more physical insight into the proximity effect in such devices. As far as the applications are concerned, the precision of the above calculation shows that the overall process is under control, and the spread in characteristics low.

Reproducible HTSc junctions have been produced by ion-beam irradiation, whose characteristics can be adjusted precisely on a wide range of temperatures, and are suitable for many applications, such as superconducting quantum interference devices and RSFQ logic, with a high degree of on-chip integration and complexity. A computation has been developed to model the junction geometry: The proximity effect makes the actual size of the device much smaller than a naive estimate from the defects distribution.

The authors gratefully acknowledge O. Kaitasov and S. Gautrot for the ion irradiation made at IRMA-CSNSM (Orsay-France), E. Jacquet, F. Lalu, and L. Leroy for technical support.

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